

Spectroscopic Ellipsometry on Ta₂O₅/SiO₂ films

(CoaCh update on optical characterization)

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Coordinated by prof. F. Vetrano
(Urbino University and INFN Firenze)

Aim:

- 1) to find the relation between coating mechanical and optical properties
- 2) to understand how mechanical/optical properties depend on chemistry/structure/morphology of the coating.

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Structure / Morphology

- Topmost surface
- Film (thickness uniformity, degree of amorphization)
- Inner interface (mixing)
- Substrate

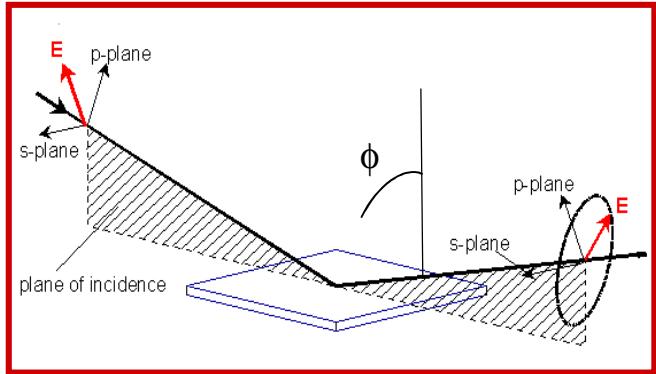
Optical Properties
Dielectric function vs wvl

Mechanical properties

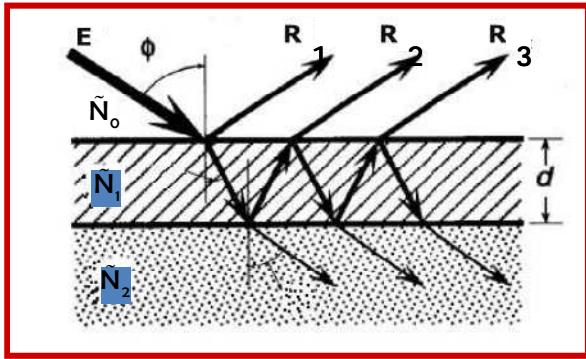
- Q
- Losses
- Young's modulus

Spectroscopic Ellipsometry

from isotropic samples



Ambient / film / substrate



$$\begin{pmatrix} E_p^{out} \\ E_s^{out} \end{pmatrix} = \begin{pmatrix} R_p & 0 \\ 0 & R_s \end{pmatrix} \begin{pmatrix} E_p^{in} \\ E_s^{in} \end{pmatrix}$$

$$\rho = \frac{R_p}{R_s} = \left| \frac{R_p}{R_s} \right| e^{i(\delta_{rp} - \delta_{rs})} = \tan \Psi e^{i\Delta}$$

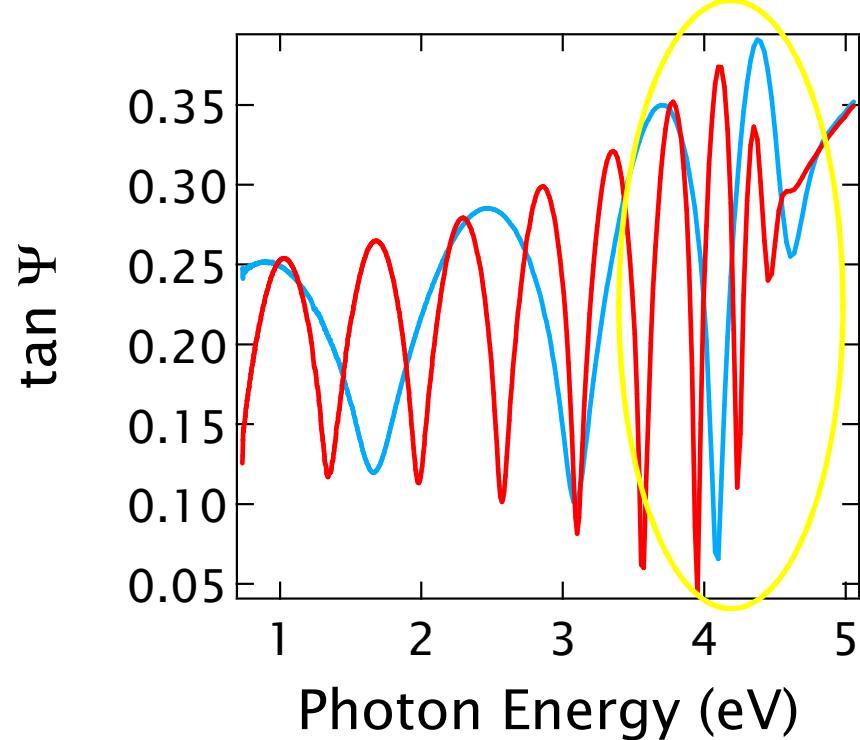
$$\rho = \tan \Psi e^{i\Delta} = \frac{R_p}{R_s} = \frac{r_{0,1}^p + r_{1,2}^p e^{-2i\beta}}{1 + r_{0,1}^p r_{1,2}^p e^{-2i\beta}} \cdot \frac{1 + r_{0,1}^s r_{1,2}^s e^{-2i\beta}}{r_{0,1}^s + r_{1,2}^s e^{-2i\beta}}$$

$$\beta = 2\pi \frac{d}{\lambda} \sqrt{\tilde{N}_1^2 - \tilde{N}_0^2 \sin^2 \Phi}$$

Non destructive

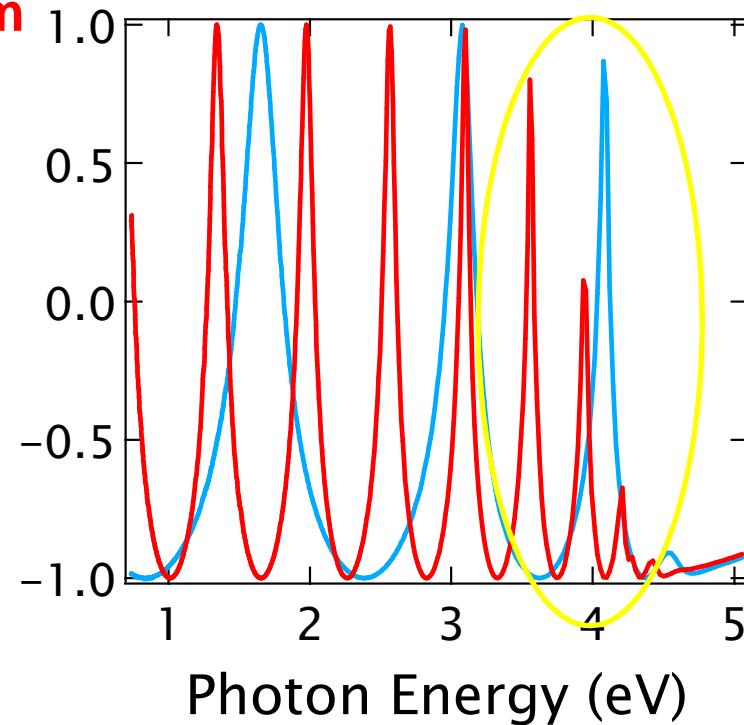
Ta_2O_5 (ATFilms) on SiO_2 corning substrates

60° incidence



200 nm

500 nm



$$\rho = \rho(\tilde{N}_0, \tilde{N}_1, \tilde{N}_2, d, \lambda, \phi)$$

Complex function of 9 real arguments

Comparison with simulations needs a model of the optical system

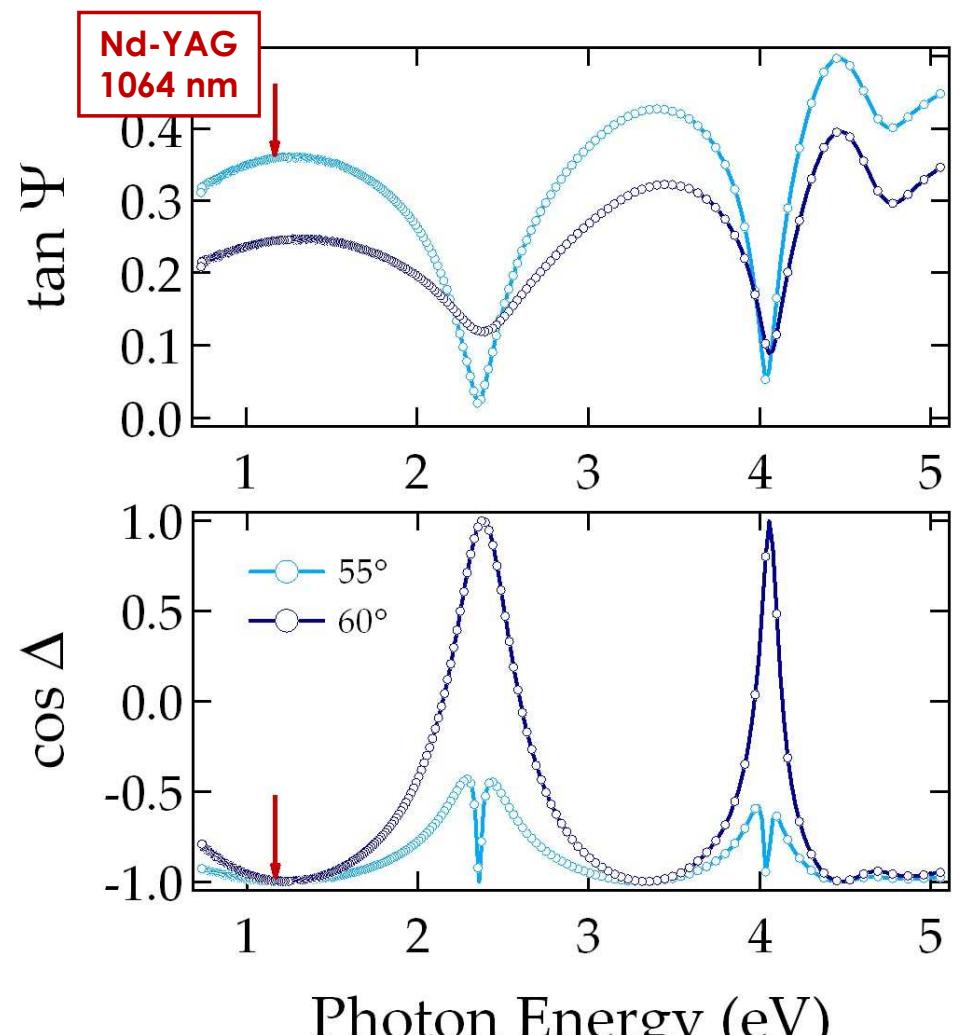
If ambient and substrate properties are known with precision
you really need
“only” n,k and thickness of the film

- Is your film really ideal ?**
- Surface ?
 - Substrate/film interface?
 - bulk defects?

Minimizing MSE

$$MSE = \frac{1}{2N-M} \sum_{i=1}^N \left[\left(\frac{\Psi_i^{\text{mod}} - \Psi_i^{\text{exp}}}{\sigma_{\Psi,i}^{\text{exp}}} \right)^2 + \left(\frac{\Delta_i^{\text{mod}} - \Delta_i^{\text{exp}}}{\sigma_{\Delta,i}^{\text{exp}}} \right)^2 \right] = \frac{1}{2N-M} \chi^2$$

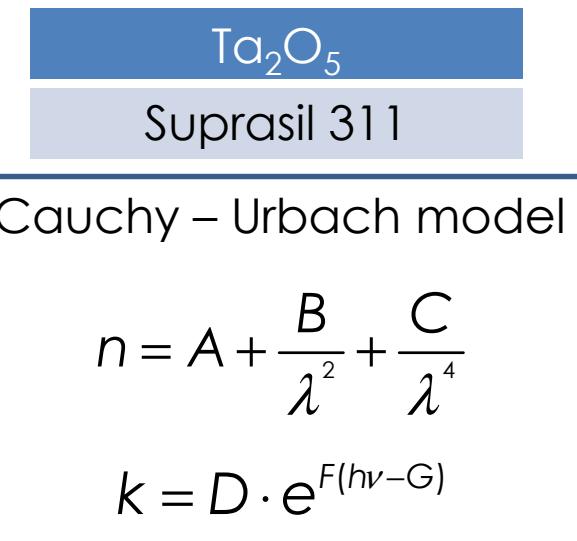
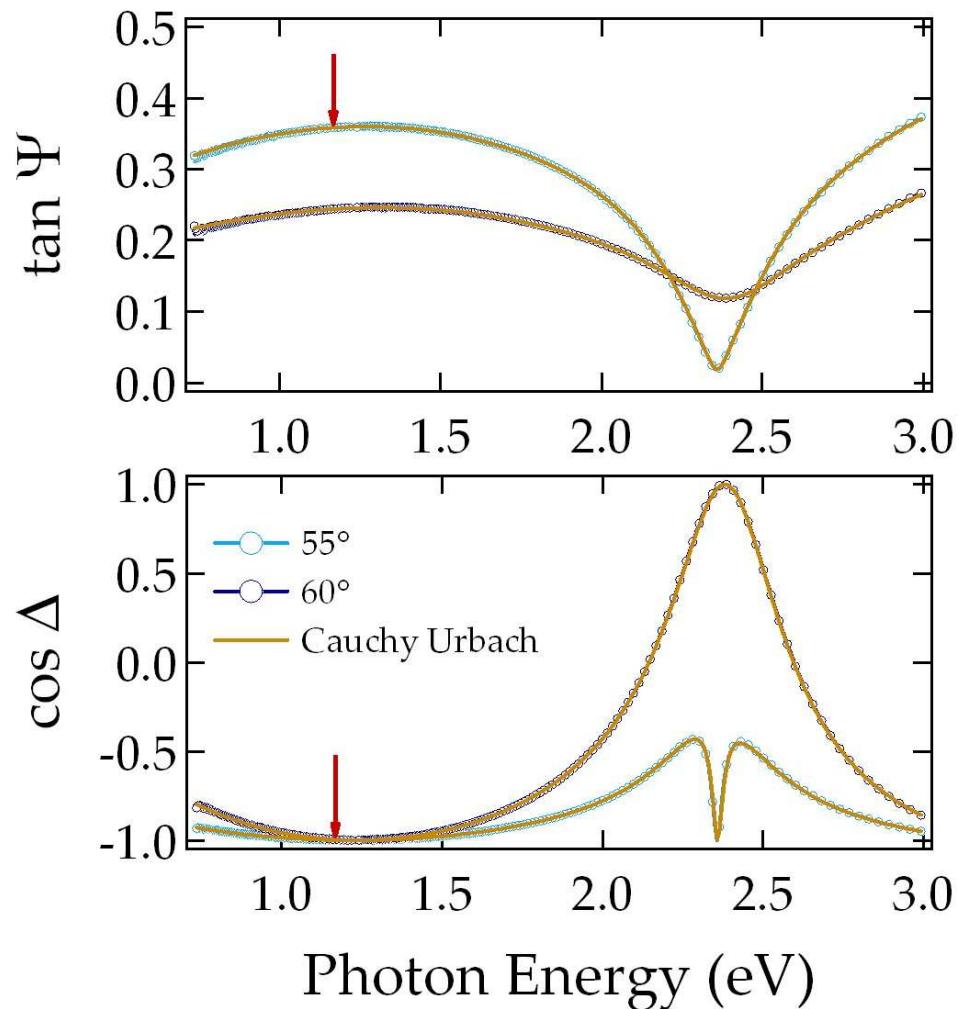
Ta₂O₅ (LMA) on Suprasil(Heraeus)
nominal thickness: 131 nm



Below Above Suprasil Brewster's Angle

Transparency region: thickness and n

No surface, no interface...



Ta_2O_5 thickness $\sim 134 \text{ nm}$

$\text{Ta}_2\text{O}_5 n@1064\text{nm} = 2.057$

$\text{Ta}_2\text{O}_5 k@1064\text{nm} \sim 8 \cdot 10^{-4}$

MSE = 5.05

R. Flaminio et al.
Class. Quantum Grav. **27** (2010) 084030

Optical index ~ 2.06
Monolayer absorption $\sim 1.2 \text{ ppm}$ (i.e. $k \approx 2 \cdot 10^{-7}$)

1. Extend the analysis to the whole energy range: 0.75-5 eV (245-1700 nm)

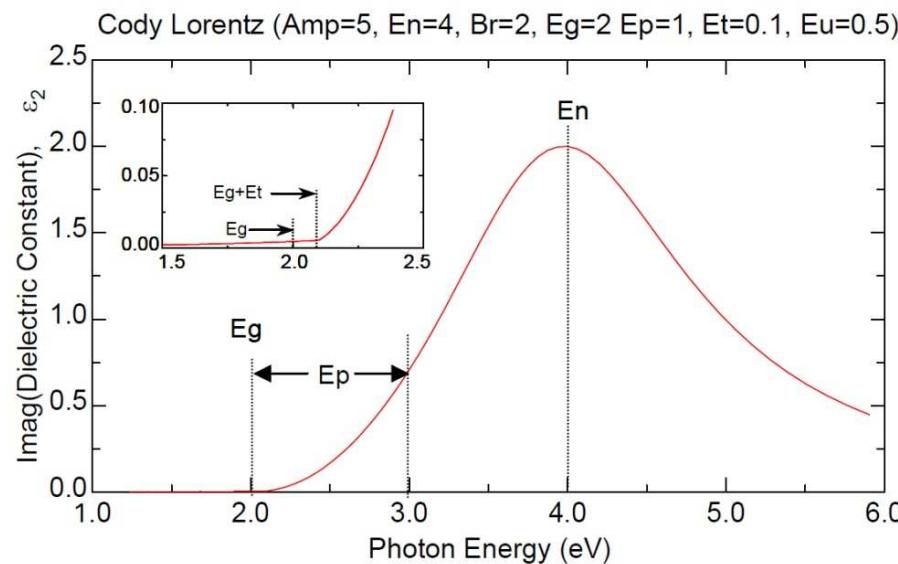
Amorphous oxides: Cody-Lorentz model + Urbach tail

[A. S. Ferlauto et al., Journal of Applied Physics 92 (2002)]

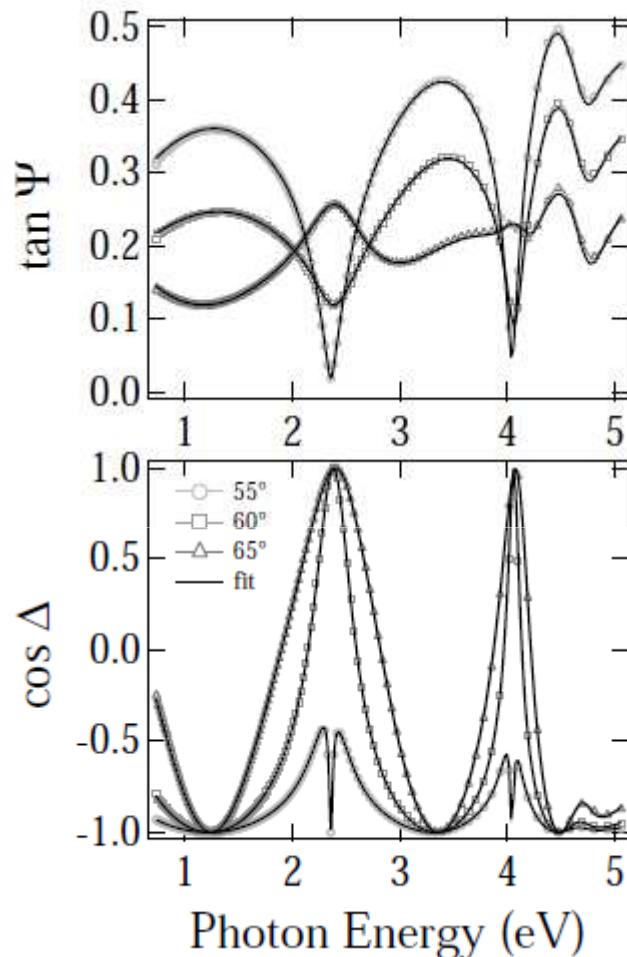
KK consistent

$$\varepsilon_2(E) = \begin{cases} \left(\frac{E_1}{E}\right) e^{\left[\frac{(E-E_g-E_t)}{E_u}\right]} & 0 < E \leq (E_g + E_t) \\ \frac{(E-E_g)^2}{(E-E_g)^2 + E_p^2} \frac{AE_0\Gamma E}{[(E^2 - E_0^2)^2 + \Gamma^2 E^2]} & E > (E_g + E_t) \end{cases}$$

$$\varepsilon_1(E) = \varepsilon_1(\infty) + \frac{2}{\pi} P \int_{E_g}^{\infty} \frac{\xi \varepsilon_2(\xi)}{\xi^2 - E^2} d\xi$$



2. The “simplest model” : Roughness layer + transition layer



Roughness layer ~ 0.25 nm

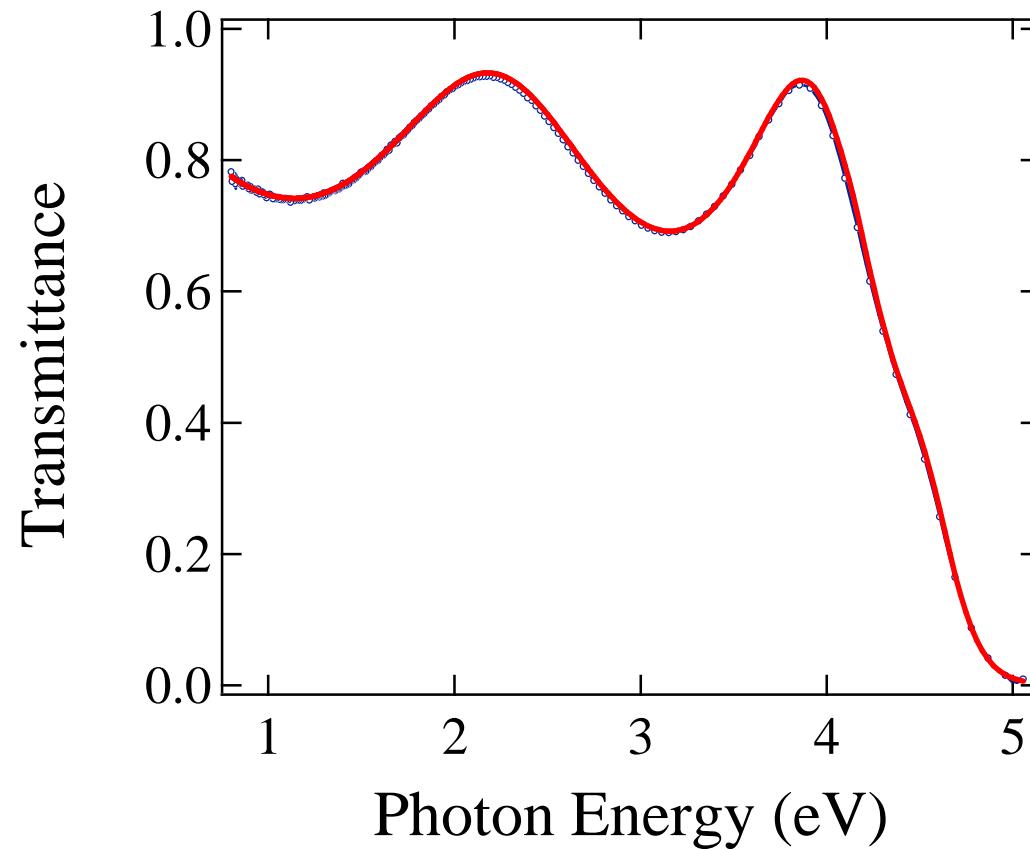
Ta₂O₅ ~ 131 nm

Intermix 50:50 ~ 6 nm

Suprasil 311

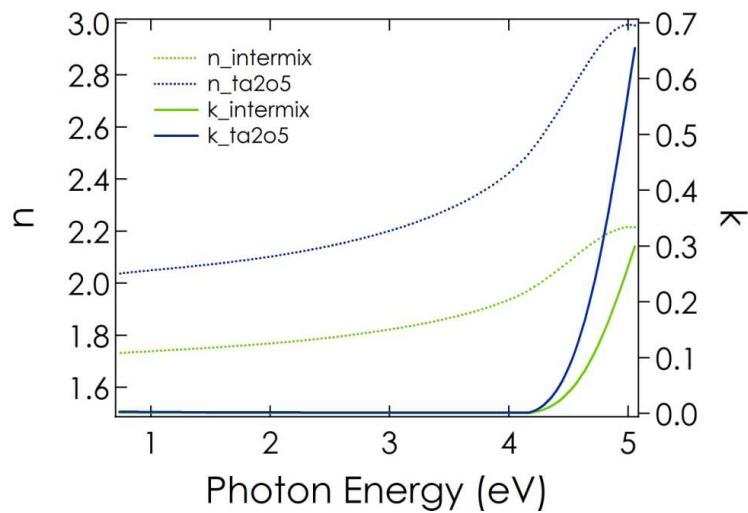
MSE = 10.15

The model fits transmittance measurements too

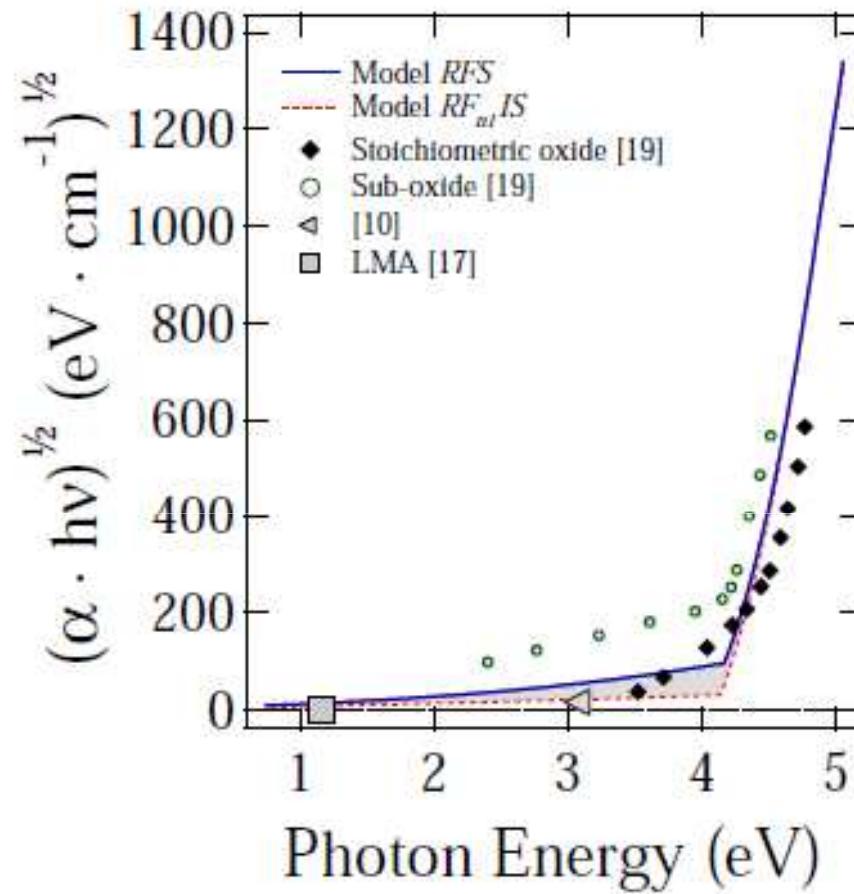


Tauc plot

M. Prato et al. to appear on *Thin Solid Films*



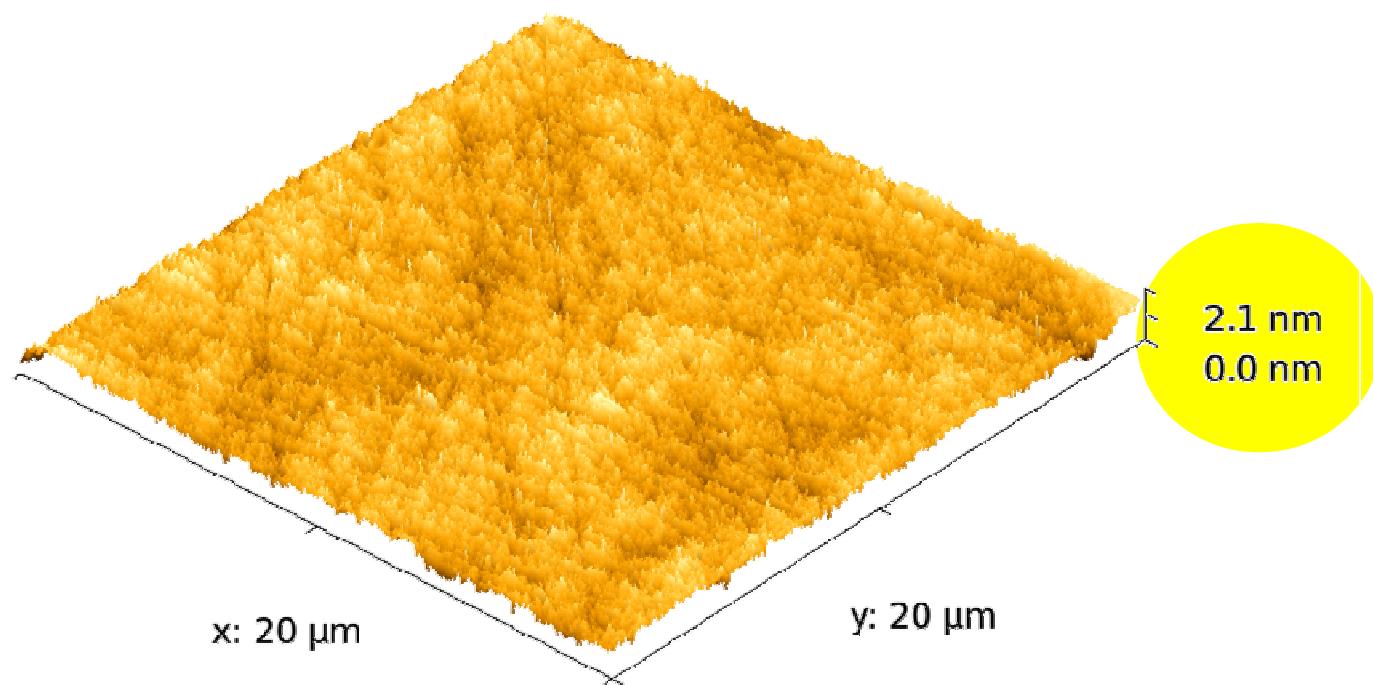
**$n = 2.057$
@1064 nm**



Gap 4.11-4.17 eV
Sub-stoichiometric

Surface layer Morphology

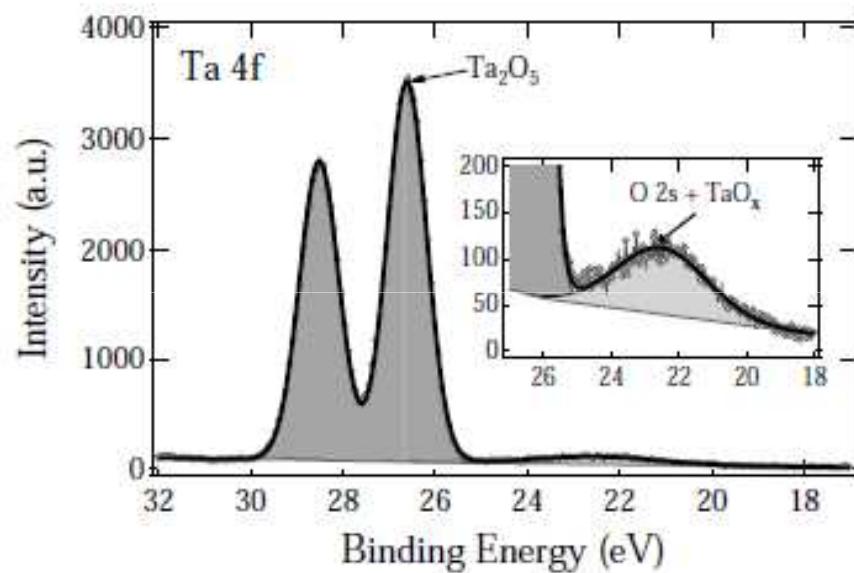
Atomic Force
Microscopy (AFM)



RMS roughness ~ 0.2 nm

Surface region chemical composition XPS

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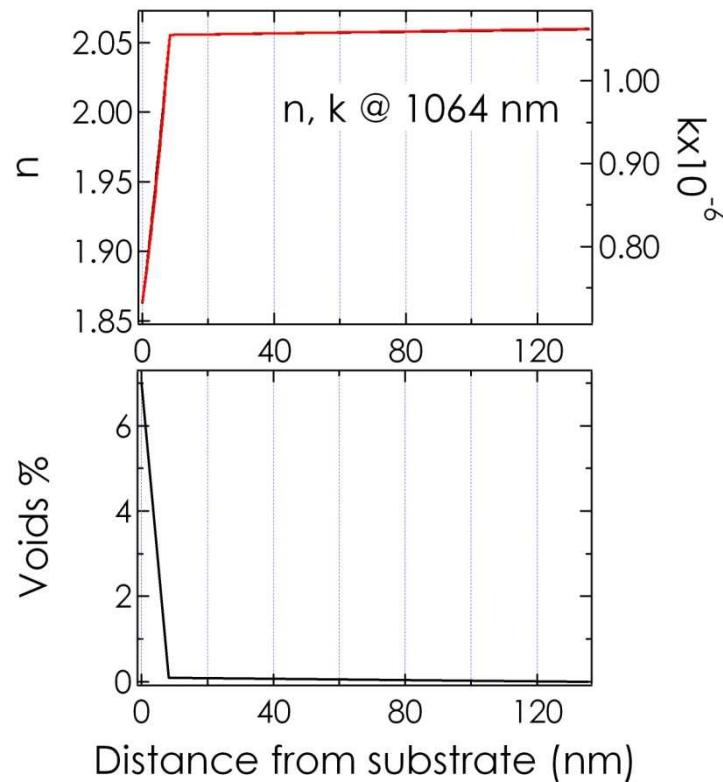
The low BE peak in the XPS spectrum is likely due to O_{2s} photoelectrons and to non-stoichiometric Ta₂O₅ species, possibly including also metallic Ta (a few %).

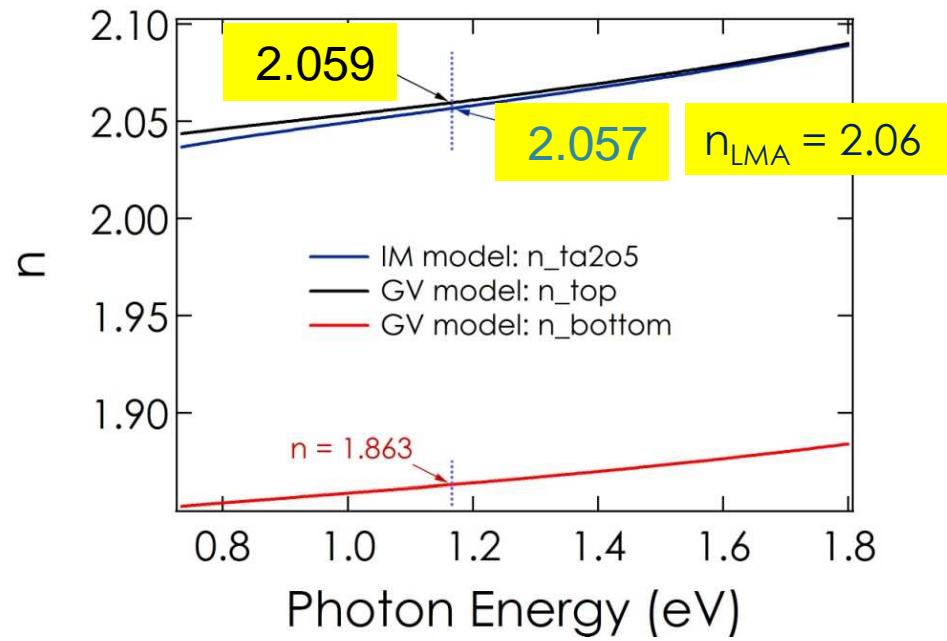
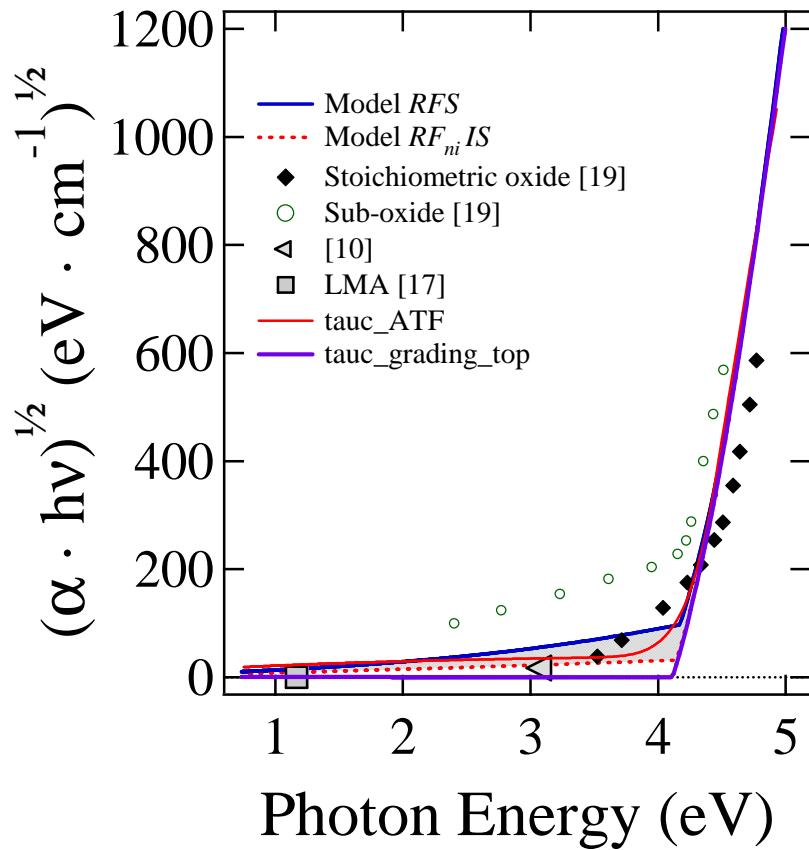
Need for higher resolution: synchrotron

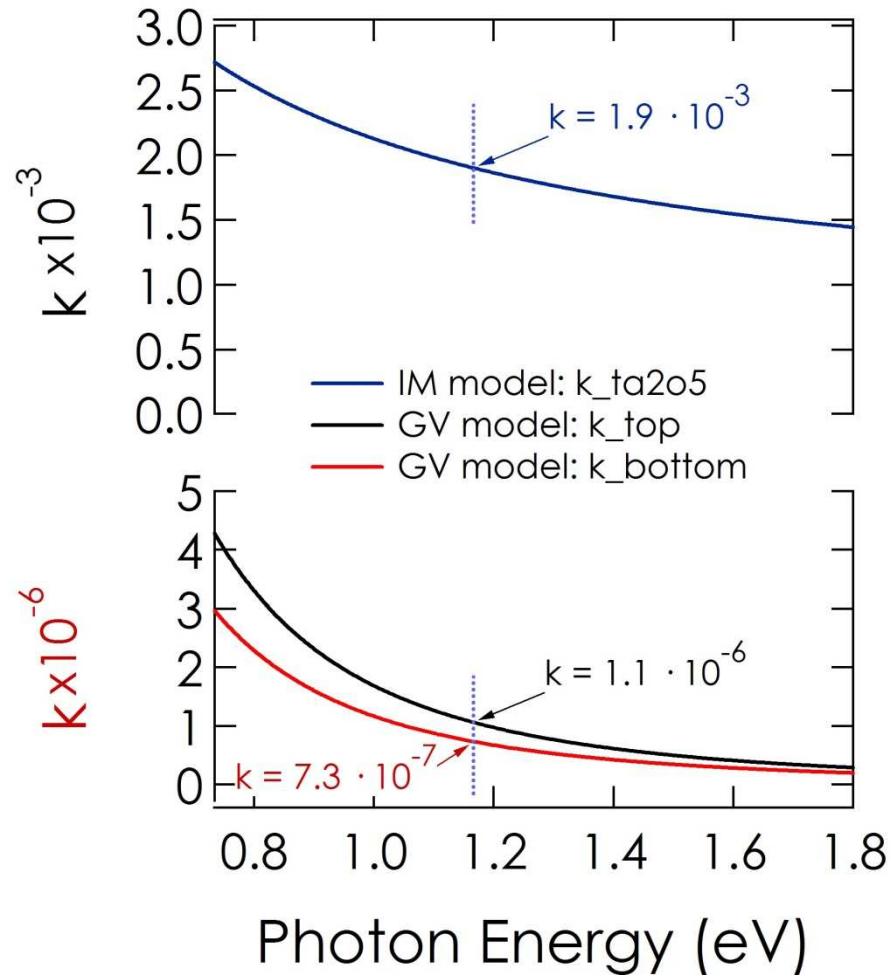
3. From “transition” to interface layer: graded distribution of voids

Roughness layer ~ 0.4 nm
Ta_2O_5 ~ 136 nm (density increasing with thickness)
Suprasil 311

MSE (voids) = 8.96
vs
MSE (IM) = 10.15







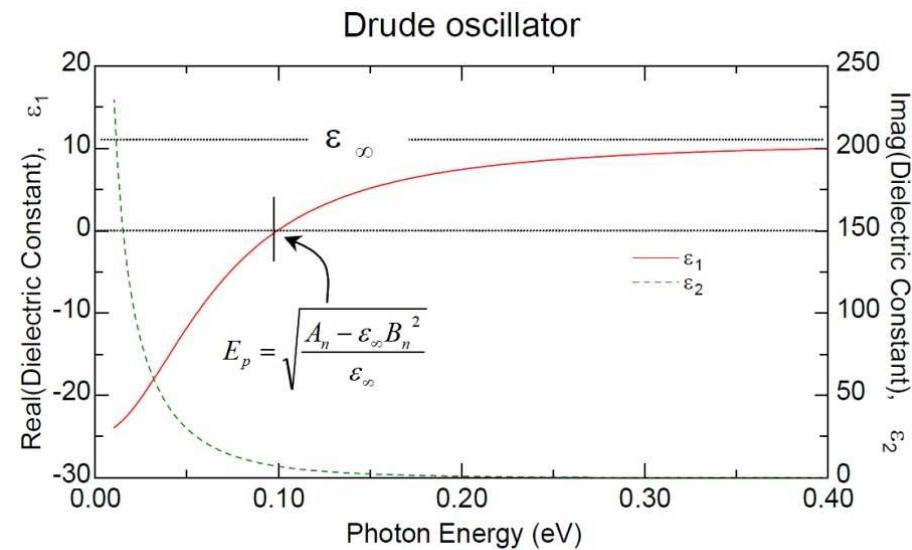
**Need for more sensitive methods
Photothermal Deflection Spectroscopy
on the same samples**

Improving (not so much) the SE interpretation

4. Including defect-related free carriers absorption @ lowest energy

Free carriers: Drude oscillator

$$\tilde{\epsilon}(E) = \epsilon_{\infty} - \frac{A}{E^2 + iBE}$$



Conclusions/Perspectives

SE:

- gap value + n value + XPS : non-stoichiometric oxide species
- Intermixing @ interface and/or diffused voids can improve the interpretation of the optical response of the Ta_2O_5 layer.
- Converging on Q-meas. vs optical measurements (SE + PTDS for k @1064 nm)
- SE investigations (broader energy range in the UV) and Higher resolution XPS (synchrotron) needed to improve models
- Interface layer: measurements on samples of reduced thickness
Independent info by TEM
-
- SE/Transmission @ at cryogenic temperatures

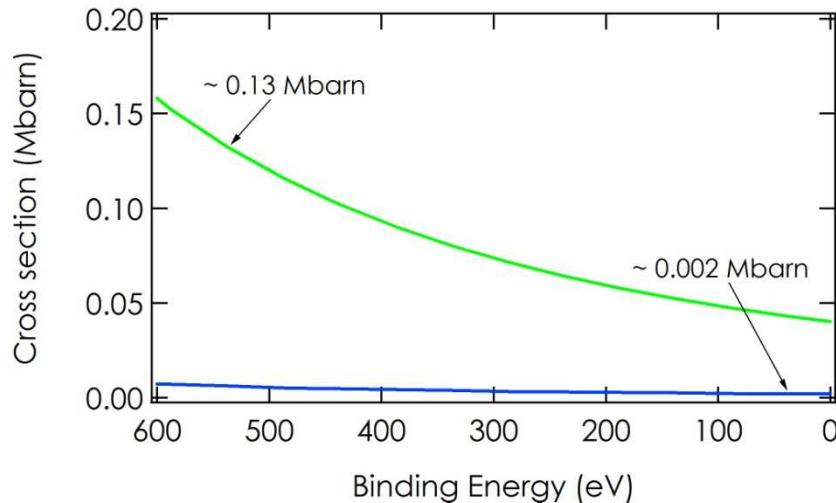
Acknowledgements

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Funding



Improving the XPS interpretation



O1s vs. O2s cross-sections

<http://ulisse.elettra.trieste.it/services/elements/WebElements.html>

